

The image features a blue background on the left and top. The Adixen logo, consisting of the word 'adixen' in blue with an orange 'x', is positioned at the top left. Below it, the text 'by Alcatel Vacuum Technology' is written in a smaller blue font. The background of the slide is a photograph of a modern building with a prominent glass-enclosed cylindrical tower. Two flagpoles with flags are visible in the foreground. The sky is a clear blue.

adixen
by Alcatel Vacuum Technology

Annecy France



**FP7 EC funded (SPAM Project)
Open Conference on
contamination
decontamination**

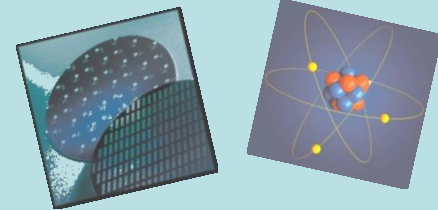
13th of SEPTEMBER 2010

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TOPICS

- Contamination in semi-conductor fab
- Decontamination applications
- Surface conditioning



Frame Work

- Supported by EC within FP7 *Pierre & Marie Curie Project (SPAM)*
- Lithography (*EUV / 193nm*) network



Location

- Annecy area :**
- ½ hour from Geneva
 - 1 hour from Lyon



Registration (SPAM consortium first)

Number of participants limited
Deadline July 9th, 2010

Contacts / Organization

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8:30 – 9:00	Registration	
9:00 – 9:30	Introduction	-L. Pfitzner (IISB) <i>ITRS vision of Contamination</i>
9:30 – 10:30	Wafer environment	-C. Martin (STM) <i>Pod and FOUP contamination analyzer: Acid and Amine impact on Defectivity and Yield</i> -S. André (STM) <i>Contamination issues and management in fab environment</i>
10:30 – 10:45	Coffee Break	
10:45 – 12:00	Contamination issue in equipment	-M. Van Kampen (ASML) <i>Molecular and particle contamination of extreme ultraviolet optics</i> -S. Blanc (40-30) <i>Cleanliness in semiconductor reactor : case of tool parts</i>
12:00 – 13:30	Lunch	
13:30 – 15:00	Photomask issues	-R. Jonckheere (IMEC) <i>Impact and mitigation of EUV reticle contamination</i> -E. Foca (AMTC) by AMTC/TPI <i>Extremely high haze growth rates on extremely clean masks exposed on extremely clean environmental conditions</i>
15:00 – 15:45	Characterization	-M. Otto (IISB) <i>Contamination Characterization Methody for Advanced Semiconductor Application – Assessment of FOUP Conditioning Equipments</i>
15:45 – 16:15	Equipment supplier	-A. Favre (AVTF) <i>Adixen solution for AMC Management</i>
16:15 - 17:30	Coffee break	Discussion



- Geneva airport : + 41 900 57 15 00
- Rental car (*Hertz*) : + 41 22 717 86 80
- Rental car Annecy (*Hertz*) : +33 4 50 51 19 89 (*near the rail station*)
- Lyon airport : + 33 826 800 826
- Taxi Annecy: + 33 6 09 99 94 95 (*Actuel Taxi*)
- Annecy Tourist office : www.lac-annecy.com
- Hotels : please contact Frédérique FAVEYROLLES





VENUE

**Les Pensières
Conference Centre
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Access to Les Pensières

